

WHAT IS CLAIMED IS:

1. A liquid crystal display device comprising a signal line, wherein the signal line comprises:

- a substrate;
- a first metal layer formed on the substrate;
- an alloy layer formed on the first metal layer;
- an insulating film having a hole on the alloy layer; and
- an electrode contacting the alloy layer through the hole of the insulating film.

2. The liquid crystal display device according to claim 1, further comprising a passivation layer having a hole on the insulating film.

3. The liquid crystal display device according to claim 1, wherein the first metal layer has a thickness ranging from about 2000 Å to about 3000 Å and formed of aluminum alloy.

4. The liquid crystal display device according to claim 1, wherein the alloy layer is formed of alloy including a first material of the first metal layer and a second material of a second metal layer formed on the first metal layer, wherein the second metal layer is subsequently removed.

5. The liquid crystal display device according to claim 4, wherein the second material comprises any one of molybdenum and chrome.

6. A method for manufacturing a liquid crystal display device, the method comprising;

- forming a first metal layer on a substrate;
- depositing a second metal layer directly on the first metal layer so as to allow an alloy layer including materials of the first and second metal layers to be formed

between the first and second layers;

removing the second metal layer remaining on the alloy layer;

etching the first metal layer in a predetermined pattern;

forming an insulating film including a hole on the alloy layer; and

forming an electrode contacting the alloy layer through the hole.

7. The method according to claim 6, further comprising forming a passivation layer including a hole on the insulating film.

8. The method according to claim 6, wherein the first metal layer has a thickness ranging from about 2000 Å to about 3000 Å and formed of aluminum alloy.

9. The method according to claim 6, wherein the second material comprises any one of molybdenum and chrome.

10. The method according to claim 9, wherein the second metal layer has a thickness ranging from about 100 Å to about 500 Å.